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Tanya Parker
(Typed or Printed Name of Person Mailing Paper or Fee)

Tanya Parker
(Signature of Person Mailing Paper or Fee)

PATENT APPLICATION
Attorney Docket No. NMTC-0771

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of)	
)	
Kevin D. MacLean et al.)	Group Art Unit: 2825
)	
U.S. Patent No.: 6,795,955 B2)	
Issued: September 21, 2004)	
)	
Application No.: 10/098,713)	Examiner: Kik, Phallaka
Filed: March 15, 2002)	Certificate
)	OCT 15 2004
For: METHOD AND APPARATUS FOR)	
IDENTIFYING AN IDENTICAL)	of Correction
CELL IN AN IC LAYOUT WITH)	
AN EXISTING SOLUTION)	

REQUEST FOR CERTIFICATE OF CORRECTION

Certificate of Correction Branch of the Publishing Division
Assistant Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

Dear Sir:

We hereby request that the above-referenced U.S Patent be corrected in the following way.

Please add the following 93 prior art references to the front page of the application. In the office action mailed February 26, 2004, the Examiner signed form 1449s for 73 IDS references filed December 2, 2002. The Examiner also cited 20 additional references. (See attached sheets.) None of these references were printed in the issued patent. Please include them in the issued patent.

In claim 8 (at column 9, line 24), please delete the words,

“the gcomplete” and replace with the words **--a complete--**

In claim 10 (at column 9, line 31), please delete the number,

“8” and replace with the number **--7--**

In claim 20 (at column 10, line 51), please delete the word,

“tantet” and replace with the word **--target--**

In claim 20 (at column 10, line 54), please delete the word,

“precedina” and replace with the word **--preceding--**

In claim 21 (at column 11, line 3), please delete the word,

“wherin” and replace with the word **--wherein--**

Please refer to enclosed PTO form PTO/SB/44.

A. Richard Park
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Davis, CA 94306
(530) 759-1661

Respectfully submitted,

By



A. Richard Park
Registration No. 41,241

Date: October 4, 2004

(Also Form PTO-1050)

UNITED STATES PATENT AND TRADEMARK OFFICE CERTIFICATE OF CORRECTION

PATENT NO : 6,795,955 B2

DATED : September 21, 2004

INVENTOR(S): Kevin D. MacLean and Roger W. Sturgeon

It is certified that an error appears in the above-identified patent and that said Letters Patent are hereby corrected as shown below:

“IDS filed February 20, 2004 and mailed with Office Action dated February 26, 2004 was scanned and references were not printed on the Issued Patent, please add:

In claim 8 (at column 9, line 24), please delete the words,

“the gcomplete” and replace with the words --a complete--

In claim 10 (at column 9, line 31), please delete the number,

“8” and replace with the number --7--

In claim 20 (at column 10, line 51), please delete the word,

“tantet” and replace with the word --target--

In claim 20 (at column 10, line 54), please delete the word,

“precedina” and replace with the word --preceding--

In claim 21 (at column 11, line 3), please delete the word,

“wherin” and replace with the word --wherein--

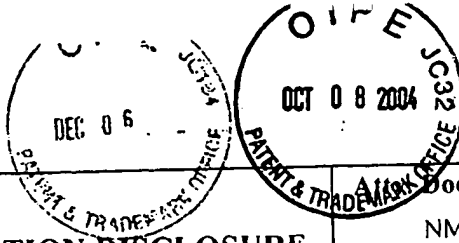
MAILING ADDRESS OF SENDER:

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PATENT NO: 6,795,955 B2

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SHEET 1 of 2

INFORMATION DISCLOSURE CITATION PTO-1449		Docket No. NMTC-0771	Serial No. 10/098,713
		Applicant MACLEAN, Kevin	
		Filing Date 3/15/2002	Group 2825
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)			
EXAMINER'S INITIALS	CITATION		
	Cobb, N., et al., "Fast, Low-Complexity Mask Design", SPIE, Vol. 2440, pp. 313-327, February 22-24, 1995.		
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	Toublan, O., et al., "Phase Aware Proximity Correction for Advanced Masks", SPIE, Vol. 4000, pp. 160-170, March 1-3, 2000.		
	Anonymous, "Parameterization For Full Shape And Rule Dependent Dissection", IPCOM000009587D, September 4, 2002 (9 pages).		

EXAMINER: Shallaka Kike

Date Considered: 2/20/2004

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

NTI Use Only: 771, 744, 1

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SHEET 2 of 2

INFORMATION DISCLOSURE CITATION PTO-1449	Docket No. NMTC-0771	Serial No. 10/098,713
	Applicant MACLEAN, Kevin	
	Filing Date 3/15/2002	Group 2825

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
<i>PR</i>	6,014,456	1/11/2000	Tsudaka	382	144	7/15/1996
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<i>PR</i>	6,298,473 B1	10/2/2001	Ono, et al.	716	21	12/3/1998
<i>PR</i>	6,339,836 B1	1/15/2002	Eisenhofer, et al.	716	5	8/24/1998
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<i>PR</i>	2002/0152454 A1	10/17/2002	Cote, et al.	716	21	6/7/2002

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Date Considered:

2/20/2004

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SHEET 1 of 4

INFORMATION DISCLOSURE
CITATION

PTO-1449

Atty. Docket No.
NMTC-0771Serial No.
10/098,713Applicant
MACLEAN, KevinFiling Date
3/15/2002Group
2818-2825

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
RE	5,182,718	1/26/1993	Harafuji, et al.	364	490	3/29/1990
RE	5,432,714	7/11/1995	Chung, et al.	364	525	9/2/1994
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EXAMINER: Shallaka KikDate Considered: 2/20/2004

EXAMINER: Initial if reference considered, whether or not citation is in conformance with
MPEP § 609; draw line through citation if not in conformance and not considered. Include
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SHEET 2 of 4INFORMATION DISCLOSURE
CITATION

PTO-1449

Atty. Docket No.
NMTC-0771Serial No.
10/098.713Applicant
MACLEAN, KevinFiling Date
3/15/2002Group
2818 2825

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITATION
<i>PD</i>	Ackmann, P., et al., "Phase Shifting and Optical Proximity Corrections to Improve CD Control on Logic Devices in Manufacturing for Sub 0.35 um 1-Line", SPIE, Vol. 3051, pp. 146-153, March 12-14, 1997.
<i>PD</i>	Lithas, "Lithas: Optical Proximity Correction Software" (2 pages). NO DATE.
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<i>PD</i>	Cobb, et al., "Fast Sparse Aerial Image Calculation for OPC", SPIE, Vol. 2621, pp. 534-544, September 20-22, 1995.
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<i>PD</i>	Fu, C.C., et al., "Enhancement of Lithographic Patterns by Using Serif Features", IEEE. Transactions On Electron Devices, Vol. 38, No. 12, pp. 2599-2603, December 1991.
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<i>PD</i>	Rieger, M., et al., "System for Lithography Proximity Compensation", Precim Company, Portland, Oregon, September 1993 (28 pages).

EXAMINER: Shallaka KiteDate Considered: 09/08/2004

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SHEET 3 of 4INFORMATION DISCLOSURE
CITATION

PTO-1449

Atty. Docket No.

NMTC-0771

Serial No.

10/098,713

Applicant

MACLEAN, Kevin

Filing Date

3/15/2002

Group

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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

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EXAMINER: Shallaka WikeDate Considered: 2/22/2004

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SHEET 4 of 4INFORMATION DISCLOSURE
CITATION

PTO-1449

Atty. Docket No.
NMTC-0771Serial No.
10/098.713Applicant
MACLEAN, KevinFiling Date
3/15/2002Group
2818 2825

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
<i>PD</i>	JP 3-80525	4/5/1991	JP	H01L	21/27	<input type="checkbox"/>	<input type="checkbox"/>
<i>PD</i>	WO 00/67074 A1	11/9/2000	WO	G03F	7/20	<input checked="" type="checkbox"/>	<input type="checkbox"/>
<i>PD</i>	WO 02/29491 A1	4/11/2002	WO	G03F	11/4	<input checked="" type="checkbox"/>	<input type="checkbox"/>
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<i>PD</i>	WO 97/38381	10/16/1997	WO	G06F	17/50	<input checked="" type="checkbox"/>	<input type="checkbox"/>
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<i>PD</i>	WO 99/14637 A1	3/25/1999	WO	G03F	9/00	<input checked="" type="checkbox"/>	<input type="checkbox"/>
<i>PD</i>	WO 99/14638 A1	3/25/1999	WO	G03F	9/00	<input checked="" type="checkbox"/>	<input type="checkbox"/>

EXAMINER: *Shallaker Mike*Date Considered: *2/20/2004*

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Notice of References Cited

Application/Control No.

10/098,713

Applicant(s)/Patent Under

Reexamination

MACLEAN ET AL.

Examiner

Phallaka Kik

Art Unit

2825

Page 1 of 2

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-5,696,693 ✓	12-1997	Aubel et al.	716/8
	B	US-2002/0152449 ✓	10-2002	Lin, Chin-hsen	716/17
	C	US-6,292,925 ✓	09-2001	Dellinger et al.	716/8
	D	US-2003/0088837 ✓	05-2003	Pierrat et al.	716/4
	E	US-2003/0068564 ✓	04-2003	Liu et al.	430/5
	F	US-6,473,881 ✓	10-2002	Lehner et al.	716/2
	G	US-2002/0048708 ✓	04-2002	Chen et al.	430/5
	H	US-6,668,367 ✓	12-2003	Cobb et al.	716/19
	I	US-6,532,585 ✓	03-2003	Petranovic et al.	716/19
	J	US-6,499,003 ✓	12-2002	Jones et al.	703/6
	K	US-6,691,296 ✓	02-2004	Nakayama et al.	716/15
	L	US-2002/0188918 ✓	12-2002	Cirit, Mehmet A.	716/9
	M	US-6,397,169 ✓	05-2002	Shenoy et al.	703/14

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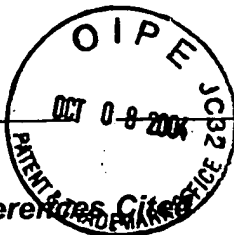
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	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
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	X	

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Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.

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**Notice of References Cited**

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10/098,713

Applicant(s)/Patent Under
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MACLEAN ET AL.

Examiner

Phallaka Kik

Art Unit

2825

Page 2 of 2

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	B	US-6,243,851 ✓	06-2001	Hwang et al.	716/10
	C	US-6,571,374 ✓	05-2003	Runyon et al.	716/5
	D	US-6,523,162 ✓	02-2003	Agrawal et al.	716/19
	E	US-6,230,299 ✓	05-2001	McSherry et al.	716/1
	F	US-5,867,396 ✓	02-1999	Parlour, David B.	716/18
	G	US-5,448,493 ✓	09-1995	Topolewski et al.	716/7
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

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	U	
	V	
	W	
	X	

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